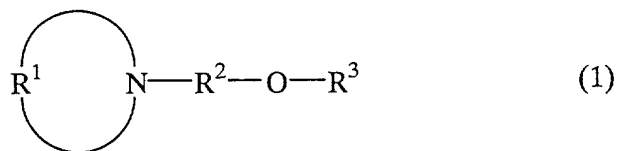


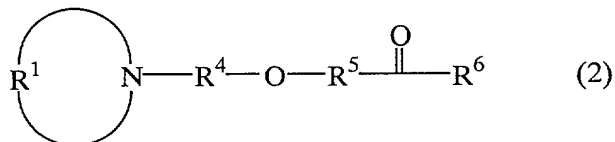
CLAIMS:

1. An amine compound of the following general formula (1):



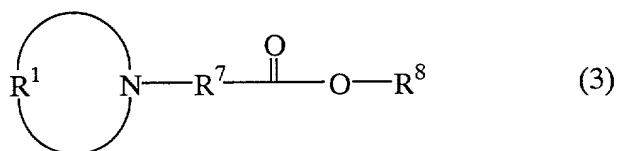
wherein R^1 is a straight or branched alkylene group of 2 to 20 carbon atoms which may contain at least one carbonyl, ether, ester or sulfide group, R^2 is a straight or branched alkylene group of 1 to 10 carbon atoms, R^3 is a straight, branched or cyclic alkyl or alkoxy group of 1 to 20 carbon atoms which may contain a hydroxy group, ether group, carbonyl group, ester group, lactone ring or carbonate group, and R^2 and R^3 , taken together, may form a ring with the oxygen atom.

2. An amine compound of the following general formula (2):



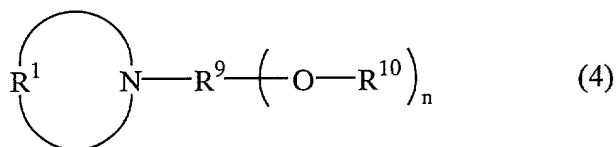
wherein R^1 is a straight or branched alkylene group of 2 to 20 carbon atoms which may contain at least one carbonyl, ether, ester or sulfide group, R^4 is a straight or branched alkylene group of 1 to 10 carbon atoms, R^5 is a single bond or a straight, branched or cyclic alkylene group of 1 to 20 carbon atoms, and R^6 is hydrogen or a straight, branched or cyclic alkyl or alkoxy group of 1 to 20 carbon atoms which may contain a hydroxy group, ether group, carbonyl group, ester group, lactone ring or carbonate group.

3. An amine compound of the following general formula
(3):



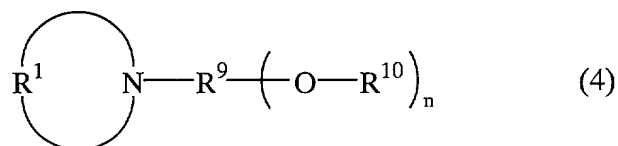
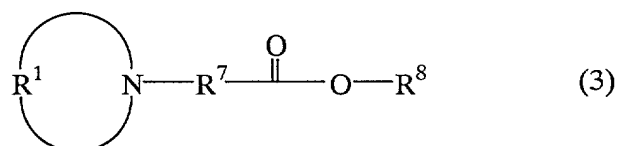
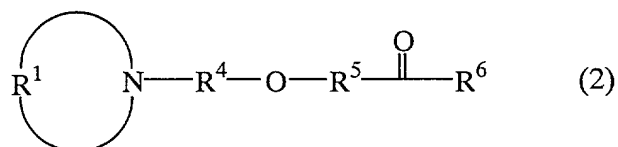
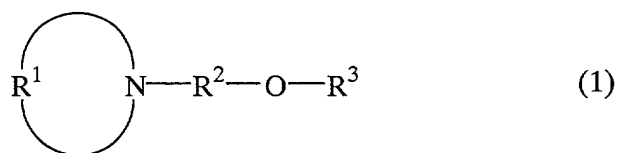
wherein R¹ is a straight or branched alkylene group of 2 to
20 carbon atoms which may contain at least one carbonyl,
ether, ester or sulfide group, R⁷ is a straight or branched
alkylene group of 1 to 10 carbon atoms, R⁸ is a straight,
branched or cyclic alkyl group of 1 to 20 carbon atoms which
may contain a hydroxy group, ether group, carbonyl group,
ester group, lactone ring or carbonate group, and R⁷ and R⁸,
taken together, may form a ring with the COO.

4. An amine compound of the following general formula
(4):



wherein R¹ is a straight or branched alkylene group of 2 to
20 carbon atoms which may contain at least one carbonyl,
ether, ester or sulfide group, R⁹ is a (n+1)-valent organic
group of 2 to 10 carbon atoms, R¹⁰ which may be the same or
different is hydrogen or a straight, branched or cyclic
alkyl or alkoxy group of 1 to 20 carbon atoms which may
contain a hydroxy group, ether group, carbonyl group, ester
group, lactone ring or carbonate group, and n is equal to 2,
3 or 4.

5. A resist composition comprising at least one of amine compounds of the following general formulae (1) to (4):



wherein R¹ is a straight or branched alkylene group of 2 to 20 carbon atoms which may contain at least one carbonyl, ether, ester or sulfide group,

R², R⁴ and R⁷ each are a straight or branched alkylene group of 1 to 10 carbon atoms,

R³ and R⁶ each are a straight, branched or cyclic alkyl or alkoxy group of 1 to 20 carbon atoms which may contain a hydroxy group, ether group, carbonyl group, ester group, lactone ring or carbonate group,

R⁵ is a single bond or a straight, branched or cyclic alkylene group of 1 to 20 carbon atoms,

R⁸ is a straight, branched or cyclic alkyl group of 1 to 20 carbon atoms which may contain a hydroxy group, ether group, carbonyl group, ester group, lactone ring or carbonate group,

R² and R³, taken together, may form a ring with the oxygen atom,

R⁷ and R⁸, taken together, may form a ring with the COO,

R⁹ is a (n+1)-valent organic group of 2 to 10 carbon atoms,

5 R¹⁰ which may be the same or different is hydrogen or a straight, branched or cyclic alkyl or alkoxy group of 1 to 20 carbon atoms which may contain a hydroxy group, ether group, carbonyl group, ester group, lactone ring or carbonate group, and

10 n is equal to 2, 3 or 4.

6. A positive resist composition comprising

(A) the amine compound of claim 5,

(B) an organic solvent,

15 (C) a base resin having an acidic functional group protected with an acid labile group, which is normally alkali insoluble or substantially alkali insoluble, but becomes alkali soluble upon elimination of the acid labile group, and

20 (D) a photoacid generator.

7. The positive resist composition of claim 6 further comprising (E) a dissolution inhibitor.

25 8. A negative resist composition comprising

(A) the amine compound of claim 5,

(B) an organic solvent,

(C') a base resin which is normally alkali-soluble, but becomes substantially alkali insoluble when crosslinked
30 with a crosslinker,

(D) a photoacid generator, and

(F) the crosslinker capable of crosslinking under the action of acid.

9. A process for forming a resist pattern comprising the steps of:

applying the resist composition of claim 5 or 6 onto a substrate to form a coating,

5 heat treating the coating and then exposing it to high-energy radiation having a wavelength of less than 300 nm or electron beams through a photo mask, and

optionally heat treating the exposed coating and developing it with a developer.